

FORM PTO-1449 (MODIFIED)		ATTY DOCKET NO.	SERIAL NO.
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT		67,200-377	Filed Herewith
(Use several sheets if necessary)		APPLICANT Fu-Liang Yang	
		FILING DATE Filed Herewith	GROUP Unknown

REFERENCE DESIGNATION U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NO.	DATE	NAME	CLASS	SUB CLASS	FILING DATE
OP	AA	5,023,671	Jun/1991	DiVincenzo et al			
OF	AB	5,119,151	Jun/1992	Onda			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
	AK						
	AL						
	AM						
	AN						

OTHER ART (including Author, Title, Date, pertinent pages, etc.)

PF	AO	Sallagoity et al, "Analysis of Width Edge Effects in Advanced Isolation Schemes for Deep Submicron CMOS Technologies", IEEE Trans. on Electron Devices, 44(11), Nov. 1996, pp. 1900-05.
OF	AP	Matsuda et al, "Novel Corner Rounding Process for Shallow Trench Isolation Utilizing MSTs (Micro-Structure Transformation of silicon). IEEE IEDM98, pp. 137-40.

EXAMINER

DATE CONSIDERED

3/18/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to application.